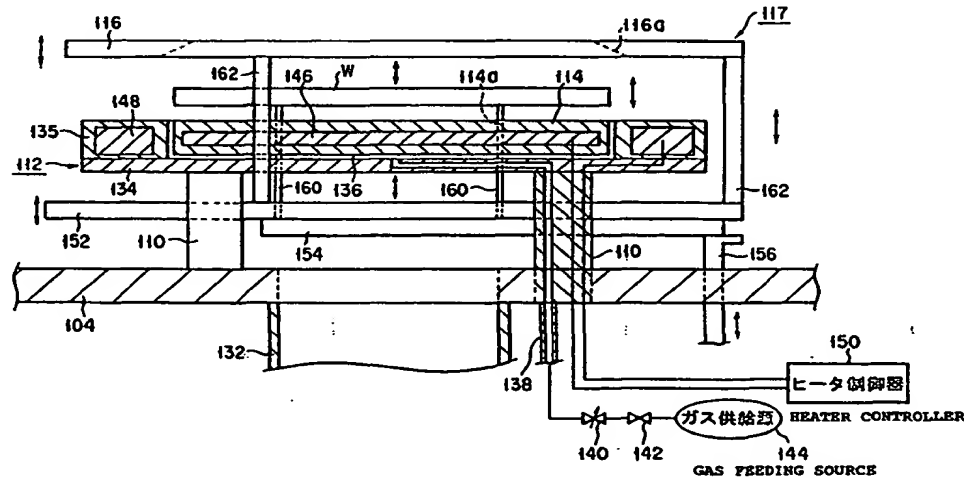


A B S T R A C T

A film deposition apparatus of the present invention includes a container forming a processing chamber for processing a target object, a mounting table which is provided in the processing chamber and on which the target object is mounted, a first heating apparatus provided in the mounting table, for heating the target object mounted on the mounting table, a first gas supply section provided in the container, for supplying processing gas into the processing chamber, the processing gas forming a high-melting-point metal-film layer on the target object mounted on the mounting table, a movable clamp for clamping a periphery of the target object and holding the target object on the mounting table, a second heating apparatus formed separately from the clamp, for heating the clamp indirectly, a gas flow path formed between the clamp and the second heating apparatus when the clamp is moved to a position where the clamp clamps the target object, and a second gas supply section for causing backside gas to flow into the gas flow path.

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<p>(54) 発明の名称 成膜装置</p>		
		
<p>(57) Abstract</p> <p>A film forming device, characterized by comprising a container forming a processing chamber in which an object is processed, a loading table which is provided in the processing chamber and on which the object is loaded, a first heating device which is provided on the loading table and heats the object loaded on the loading table, a first gas feeding part which is provided in the container and feeds into the processing chamber a processing gas for forming a metallic film layer with high melting point on the object loaded on the loading table, a movable clamp holding the object on the loading table by pressing the peripheral part of the object, a second heating device which is formed separately from the clamp and indirectly heats the clamp, a gas flow path formed at least between the clamp and the second heating device when the clamp is moved to a position where it presses the object, and a second gas feed part feeding a back side gas to the gas flow path.</p>		